



1. Title:	Acid generation in chemically amplified EUV resists
2. Full names of all authors:	T. Kozawa, S. Tagawa, H. Oizumi and I. Nishiyama

3. Abstract body:

Below the 32 nm node, the chain length of acid catalytic reactions must be suppressed to several nanometers to meet the resolution requirement. Under such circumstances, the initial yield of acids produced by exposure is critical to the formation of ultrafine patterns. Using an acid sensitive dye, the number of acid molecules generated by EUV exposure was evaluated. Based on experimental results, the acid generation mechanism is discussed.